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(54) **SPUTTER TARGET FOR A PHYSICAL VAPOR DEPOSITION CHAMBER**

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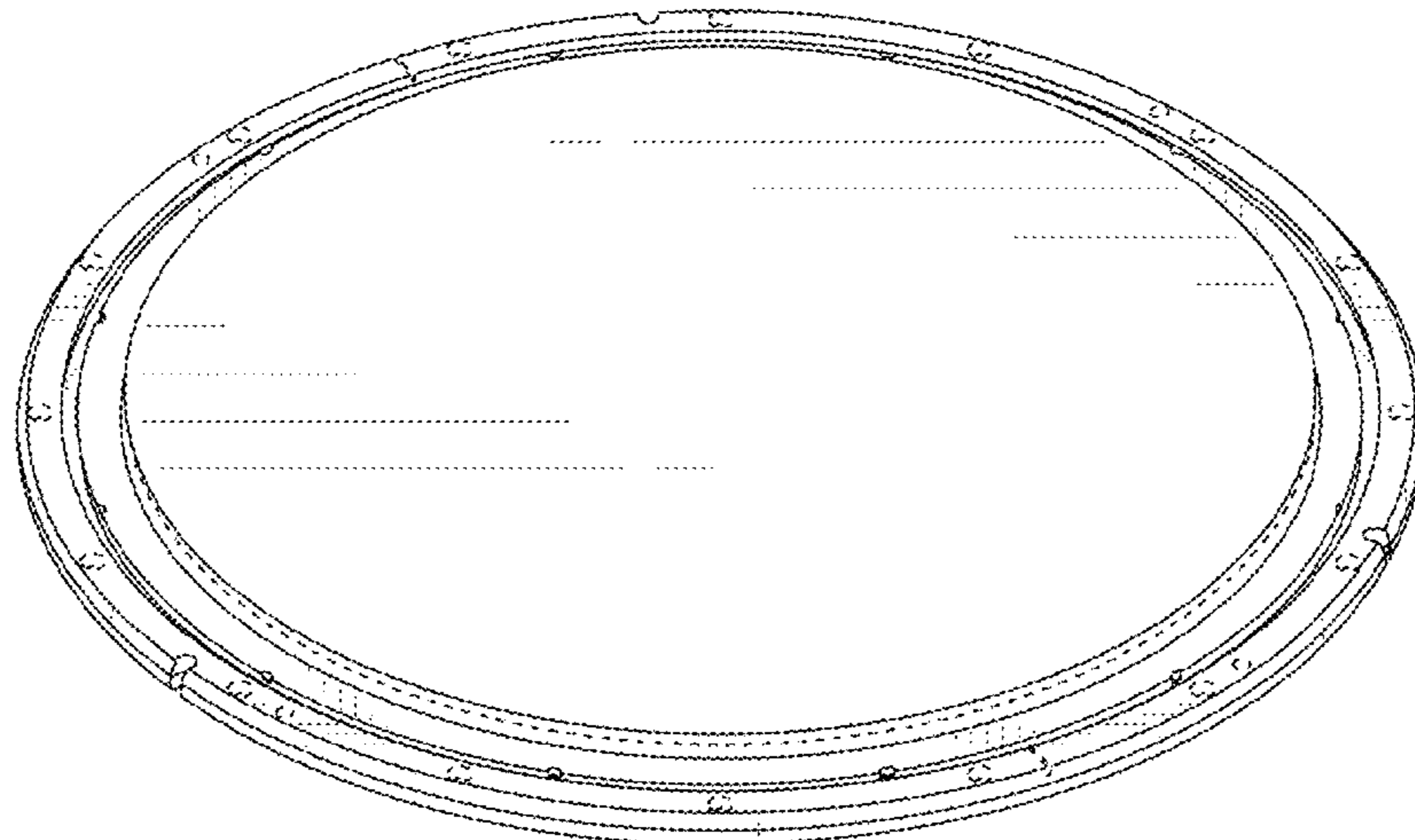
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 CPC ..... H01J 37/3414; H01J 37/3423; H01L 21/02631; H01L 2221/68363; H01L 2224/75186-75189; H01L 21/67742; H01L 21/0226; H01L 21/02263; H01L 21/02266; H01L 21/02269; H01L 21/02271; F16J 7/00; E04D 13/14; C23C 14/3407; C23C 14/35

See application file for complete search history.

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## (57) CLAIM

We claim the ornamental design for a sputter target for a physical vapor deposition chamber, as shown and described.

**DESCRIPTION**

FIG. 1 is a top isometric view of a sputter target for a physical vapor deposition chamber, according to one embodiment of the novel design.

FIG. 2 is a top plan view thereof.

FIG. 3 is a bottom plan view thereof.

FIG. 4 is a right elevation view thereof.

FIG. 5 is a left elevation view thereof.

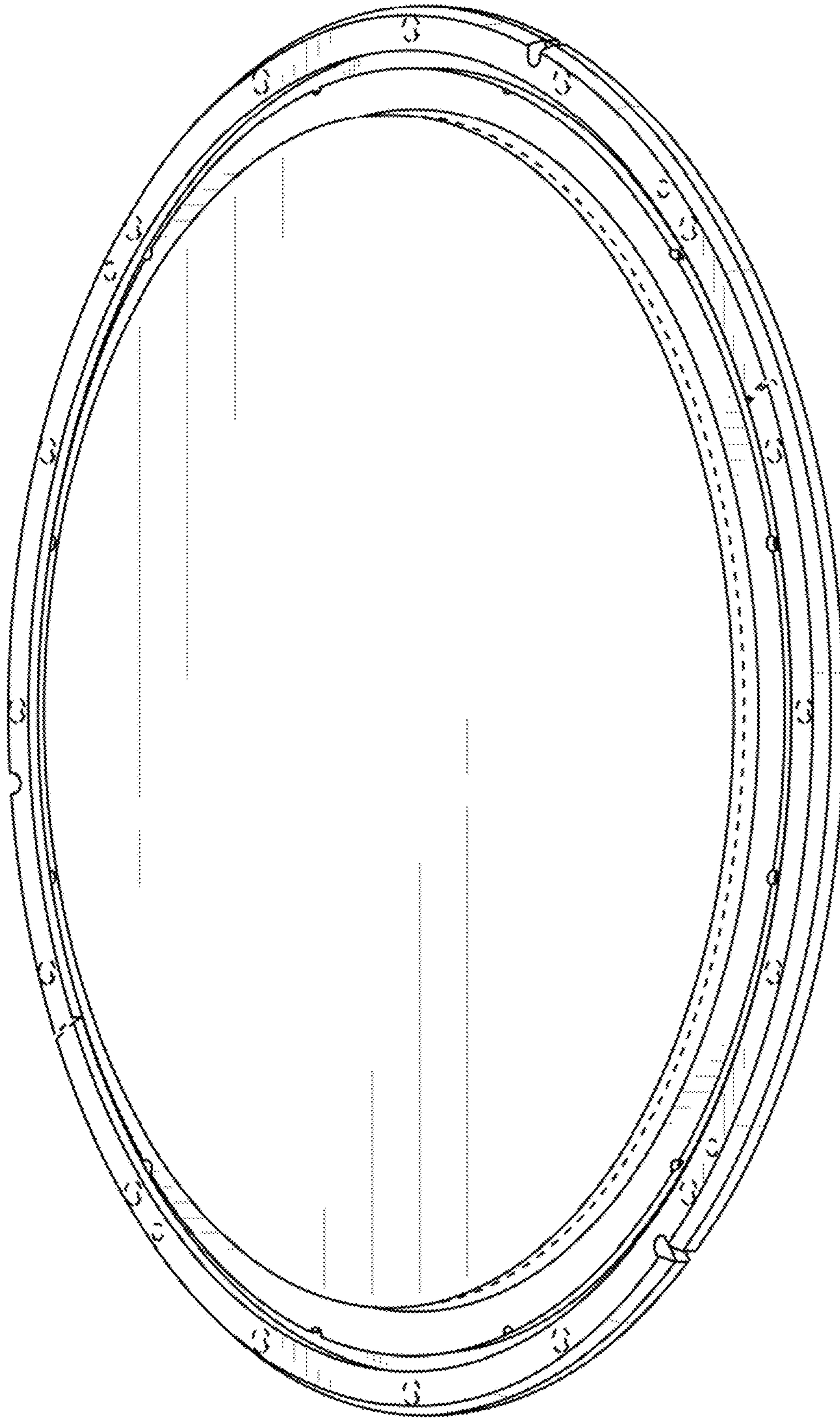
FIG. 6 is a front elevation view thereof.

FIG. 7 is a back elevation view thereof; and,

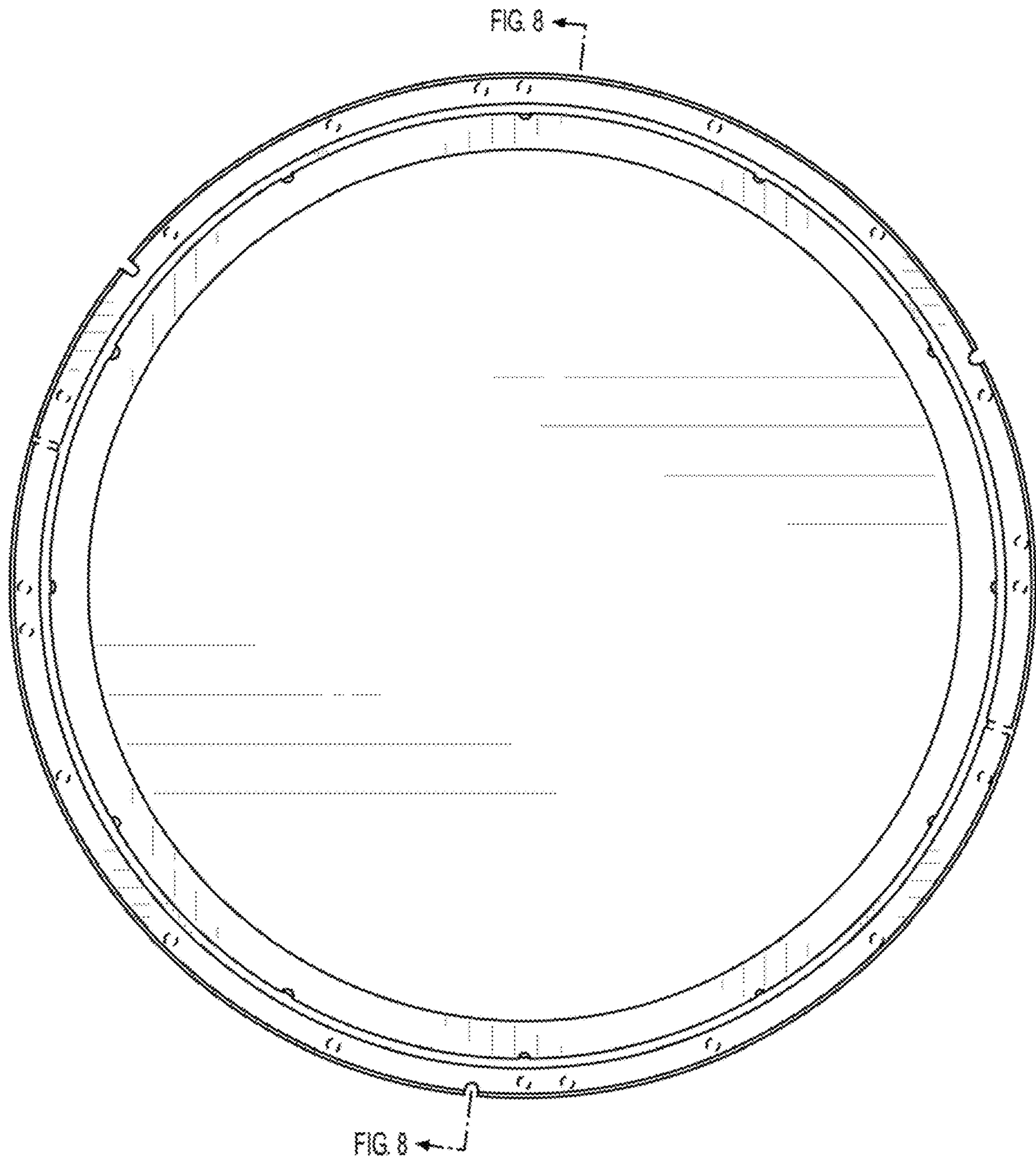
FIG. 8 is an enlarged cross-sectional view taken along line 8-8 in FIG. 2.

The broken lines in the drawings represent unclaimed environment and form no part of the claimed design.

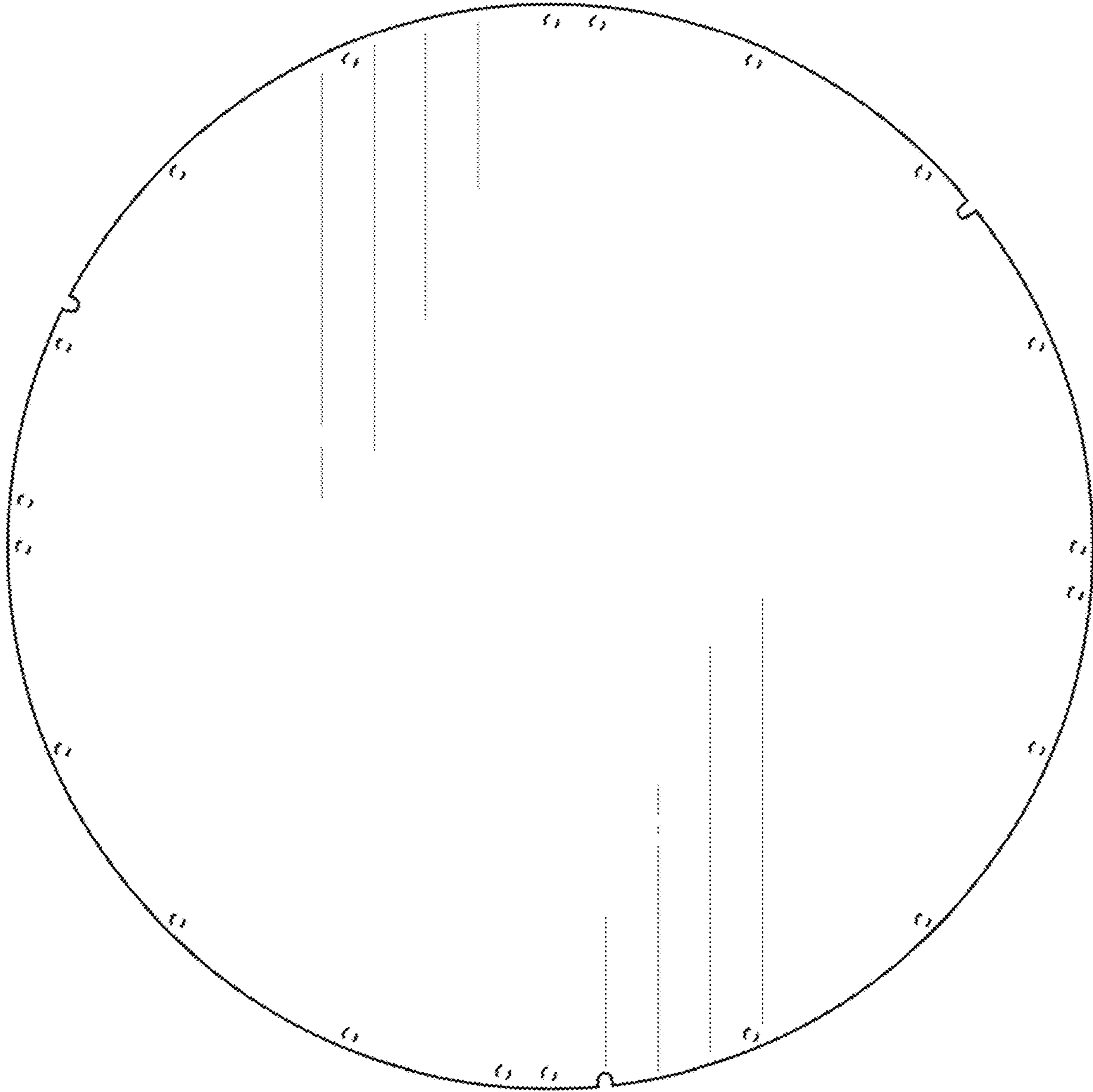
**1 Claim, 5 Drawing Sheets**



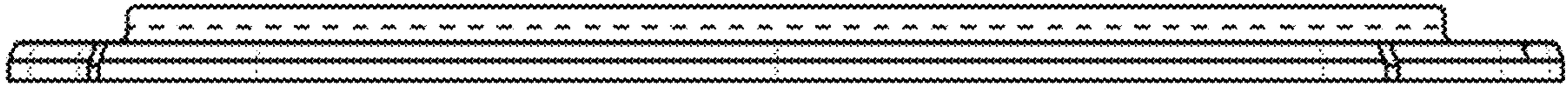
**FIG. 1**



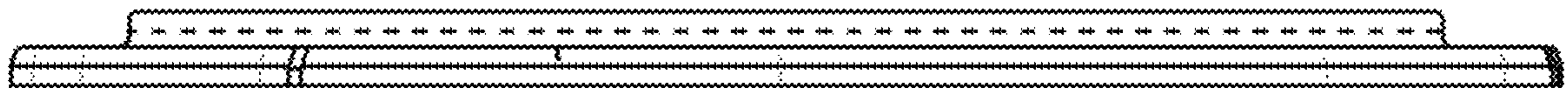
**FIG. 2**



**FIG. 3**



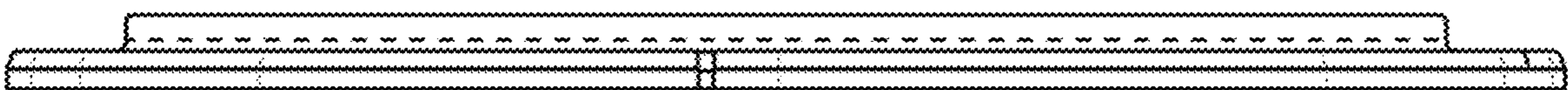
**FIG. 4**



**FIG. 5**



**FIG. 6**



**FIG. 7**



**FIG. 8**